

ABSTRACT OF THE DISCLOSURE

A polishing pad used for precise polishing of the surface of a lapped glass workpiece when a glass substrate
5 for use in data recording media is manufactured from a glass workpiece. The polishing pad comprises a base and a polishing portion laminated on the base and contacting the surface of the glass workpiece at the time of polishing. The polishing portion is formed of a foam made of a synthetic resin having
10 a 100% modulus of 11.8 MPa or less. A type of parameter representing the surface roughness of the polishing portion, namely, the maximum height (R_{max}), is 70 μm or less.